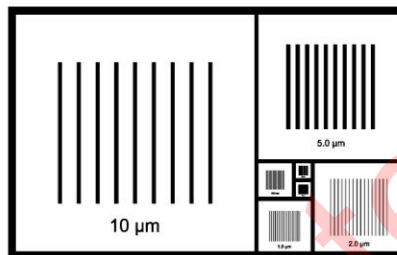


## AISthesis Products

Advanced Imaging Products for Nanotechnology,  
Engineering and Life Sciences  
PO Box 1950, Clyde NC 28721



### Wafer Level Certificate of Traceability for Pelcotec™ Critical Dimension Magnification Standard



Product Number: **Pelcotec™** 692-01 CDMS-0.1T-ISO

Customer name and contact information:

Product Description: 2.5x2.5mm, **Pelcotec™** 2mm-100nm Critical Dimension Magnification Standard



Wafer Identifier: CD-AI05

As Received Condition: New

P.O. Box 492477  
Redding, CA 96049-2477  
Tel: 530.243.2200

As Returned Condition: N/A

Date of Receipt: N/A

[www.tedpella.com](http://www.tedpella.com)

The accuracy of this product with Wafer Identifier CD-AI05 was determined using a Field Emission Scanning Electron Microscope (FE-SEM) by reference comparison to working standards traceable to the National Institute of Standards and Technology (NIST), using CP 01 FE-SEM Imaging of Critical Dimension Magnification Standards (CDMS) and CP 02 Certification of Critical Dimension Magnification Standards. Die were sampled according to method SOP 07 Sampling Die. The data applies only to the CDMS products identified in this report. All results are "as-is". Repair and/or adjustments are not possible.

Below are the ISO 17025:2017 Accredited Average 10 µm Pitch Measurements unique to Die with Wafer Identifier CD-AI05 and traceable to NIST Certified Standard CD-PG01-0211.

Line	ISO 17025:2017 Accredited Average Pitch on Wafer	Position of Measurement
0-10 µm	10.005 µm	± 7.5 µm from center
10-20 µm	10.003 µm	± 7.5 µm from center
20-30 µm	10.005 µm	± 7.5 µm from center
30-40 µm	10.003 µm	± 7.5 µm from center
40-50 µm	10.005 µm	± 7.5 µm from center
50-60 µm	10.003 µm	± 7.5 µm from center
60-70 µm	10.005 µm	± 7.5 µm from center
70-80 µm	10.003 µm	± 7.5 µm from center

Sum	80.032
Average	10.0040 $\mu\text{m}$
2-Sigma *	0.0062 $\mu\text{m}$

\* Corrected for sample size using the appropriate Student t-factor.

Measurements are reported with an uncertainty ( $k=2$ )\*\* of  $\pm 0.012 \mu\text{m}$ . Statements of Conformity are not provided in this report. Review the results and verify that they meet the requirements for the intended use. Physical damage to or contamination of the CDMS occurring after calibration may invalidate the reported measurements. Use this product at  $25^\circ\text{C} \pm 5^\circ\text{C}$  and at less than 80% RH.

\*\* Reported uncertainties represent expanded uncertainties expressed at approximately the 95% confidence level using a coverage factor of  $k = 2$ . The reported expanded measurement uncertainty is stated as the standard measurement uncertainty multiplied by the coverage factor K such that the coverage probability corresponds to approximately 95%.

Below are the Non-ISO 17025:2017 Accredited Average Pitch Measurements unique to Die with Wafer Identifier CD-AI05 and traceable to NIST Certified Standard CD-PG01-0211.

Line	Number of Lines	Position of Measurement	Non-ISO 17025:2017 Accredited Average Measured Distance (first to last line)	Non-ISO 17025:2017 Accredited Average Pitch of Wafer
2.0 mm	2	$\pm 1.00\text{mm}$ from center	2.000 mm	2.000 mm
1.0 mm	2	$\pm 0.5\text{mm}$ from center	1.000 mm	1.000 mm
0.5 mm	2	$\pm 0.25\text{mm}$ from center	0.500 mm	0.500 mm
0.25 mm	2	$\pm 0.125\text{mm}$ from center	0.250 mm	0.250 mm
5.0 $\mu\text{m}$	12	$\pm 20 \mu\text{m}$ from center	55.025 $\mu\text{m}$	5.002 $\mu\text{m}$
2.0 $\mu\text{m}$	16	$\pm 10 \mu\text{m}$ from center	30.059 $\mu\text{m}$	2.004 $\mu\text{m}$
1.0 $\mu\text{m}$	17	$\pm 5 \mu\text{m}$ from center	16.011 $\mu\text{m}$	1.001 $\mu\text{m}$
500 nm	20	$\pm 4 \mu\text{m}$ from center	9.480 $\mu\text{m}$	498.9 nm
250 nm	21	$\pm 2.5 \mu\text{m}$ from center	4.990 $\mu\text{m}$	249.5 nm
100 nm	52	$\pm 2.5 \mu\text{m}$ from center	5.092 $\mu\text{m}$	99.8 nm

The average pitch is derived from the stated length that was determined using measurements (taken center-to-center) over the stated number of lines (i.e., length divided by the number of lines minus one).

Date of Analysis: December 2<sup>nd</sup>, 2024

Equipment used:

Instrument	Model	Serial #	Resolution	Repeatability	Temperature	Humidity	Reference
FE-SEM	FEI Apreo 2	9958357	0.9nm	0.030%	$23.3 \pm 0.3^\circ\text{C}$	$42.5 \pm 1.5\%$	CD-PG01-0211

Location: AlStthesis Products, Inc., PO Box 1950, Clyde North Carolina 28721.

Notes:

D.S. Finch  
Certified by

\_\_\_\_\_  
Signature

H. Haehlen  
Authorized by

\_\_\_\_\_  
Signature

December 2<sup>nd</sup>, 2024  
Date report issued.

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P.O. Box 1950, Clyde, North Carolina 28721 Tel: 828.627.6555 E-mail: [CDMS@aistthesisproducts.com](mailto:CDMS@aistthesisproducts.com)

End of report.